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(54) **METHOD FOR HIGH-RESOLUTION ETCHING OF THIN LAYERS WITH ELECTRON BEAMS**

VERFAHREN ZUM HOCHAUFLÖSENDEN ÄTZEN DÜNNER SCHICHTEN MITTELS
ELEKTRONENSTRAHLEN

PROCEDE DE GRAVURE AVEC UNE HAUTE RESOLUTION DE COUCHES MINCES AU MOYEN
DE FAISCEAUX D' ELECTRONS

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